

SPECIFICATION AMENDMENTS

IN THE SPECIFICATION:

1. Please amend the paragraph starting at Page 13, line 11 of the specification to read:

In ~~one~~the embodiment depicted in FIGURE 3, pellicle 50 may be located between photomask 54 and ~~an~~ imaging lens 55(not expressly shown) of a photolithography system. ~~A radiant~~Radiant energy source 57(not expressly shown) emits a wavelength of light toward photomask 54. ~~and the~~ The incident light first passes through the transparent openings formed by patterned layer 53 of photomask 54 and then passes through film 51. The incident light on photomask 54 diffracts beams that create a Fraunhofer diffraction pattern. Each peak of the Fraunhofer pattern corresponds to the openings' Fourier expansion series terms. If light having large diffraction angles is collected by the imaging lens 55, the projected image will consist of an increased amount of Fourier expansion series terms. The zero term of the series expansion contains only the intensity of the illumination and not the spatial information of the opening. At least the first-order terms are required for some dimensions of the openings to be reproduced in the image. The greater number of terms that are retained in the expansion, the more likely that the image will resemble the shape of the opening.